

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

re Application of:

CHIH-CHIEN LIU, et al.

Serial No. 09/546,174

Filed: April 11, 2000

HIGH DENSITY PLASMA CHEMICAL For:

VAPOR DEPOSITION PROCESS

Examiner: R. SERGENT

Art Unit: 1711

RECEIVED

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TC 1700

## AMENDMENT AFTER FINAL OFFICE ACTION

**Assistant Commissioner of Patents** Washington, D.C. 20231

Dear Sir or Madame:

Attached please find copies of references that were discovered by our client only after the Final Office Action was entered. Please include these copies of US Patent numbers 5,854,126 and 5,219,788 in the file.

October 8, 2002

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